

KEMET POLISHING CLOTHS

Chemo-textile Cloths.

**PSU-S /
PSU-M /
PSU H:** These soft, medium and hard chemo-textile cloths are for smoothing and polishing operations. Commonly used with Kemet Diamond Compound 14 micron and finer.



PAD-K: The ultra-hard chemo-textile cloth used where fast cutting is needed. Used with Kemet Diamond Compound 25 micron and finer. Also available perforated.



Silk Type Cloths.

MSFL: Will polish metal flat, and to a mirror finish. Best results are obtained when used with Kemet Diamond Compound or Diamond Suspension 3 micron and finer. Water resistant adhesive (oil resistant available).



MSF: Similar to MSFL, but with a thicker, softer adhesive backing and plastic barrier which is resistant to most fluids.



MSR: Similar to MSFL with rigid plastic backing.



MST: An extra hard, rigid silk cloth for increased cutting action.



ULP: A heavy duty nylon pad for high stock removal.



Kemet Chemo-textile Cloths

Manufactured to the highest standards with accurately controlled uniform thickness. Self-adhesive, and available in soft (**PSU-S**), medium (**PSU-M**), hard (**PSU-H**) and extra hard (**PAD-K**) formats. **Chem Cloth** is also available for Chemo-mechanical Polishing.

Pack of 10	75mm dia	150mm dia	200mm dia
Type	Code	Code	Code
PSU-S	341034	341013	341014
PSU-M	341021	341007	341008
PSU-H	341050	341051	341052
PAD-K	341037	341020	341017

Pack of 10	250mm dia	300mm dia	380mm dia
Type	Code	Code	Code
PSU-S	341026	341015	341016
PSU-M	341009	341010	341011
PSU-H	341053	341054	341055
PAD-K	341028	341039	341024

Kemet Silk-Type Cloths

Kemet silk-type cloths have been developed for finishing metal specimens and components.

The five types available are **MSFL**, **MSF**, **MSR**, **MST** and **ULP**.

Pack of 10	150mm dia	200mm dia	250mm dia
Type	Code	Code	Code
MSFL	341751	341752	341754
MSF	341741	341742	341747
MSR	341701	341702	341707
MST	341761	341762	341764
ULP	-	341971	341972

Pack of 10	300mm dia	380mm dia
Type	Code	Code
MSFL	341755	341756
MSF	341744	341745
MSR	341704	341705
MST	341763	341765
Pack of 5 ULP	341973	-

KEMET POLISHING CLOTHS

Kemet Nap Type Cloths

For final polishing stages of preparation, Kemet Nap Type Cloths are available with a range of softness and nap length. They give a more gentle polish, and are ideal for softer specimens and components. All cloths are self-adhesive unless marked 'plain'.

Type	Code
NMH	341236
Selvyt SR	341305

Nap Type Cloths Plain (Roll Stock)

Selvyt: Supplied on a 1400mm wide roll, priced per metre length.

NMH: Supplied on a 50" wide roll, priced per yard length.

Pack of 10	150mm dia	200mm dia	250mm dia
Type	Code	Code	Code
NFC	341207	341208	341225
MBL	341721	341722	341726
MRE	341711	341712	341716
NSH-B	341256	341257	341246
NLH	341241	341205	341247
NMH	341222	341223	341237
Chem H	341779	341782	341783

	300mm dia	380mm dia
Type	Code	Code
NFC	341210	341211
MBL	341724	341725
MRE	341714	341715
NSH-B	341203	341243
NLH	341206	341248
NMH	341224	341221
Chem H	341784	341865

NFC: Synthetic flock sprayed on cotton carrier. Can be used with 1 micron Kemet Diamond Compound after a smoothing operation on ASF to produce a mirror finish on soft materials. Colour: Green.



MBL: Synthetic flock sprayed on cotton carrier. Used with 3 micron Kemet Diamond Compound after 6 micron ASF-AW stage. Colour: Black.



MRE: Synthetic flock sprayed on a flexible waterproof carrier. A more heavy duty cloth for use with 6 micron Kemet Diamond Compound and finer. Colour: Red.



NSH-B: A short nap cloth with woven backing used for metallographic and some optical polishing operations. Commonly used with Kemet Diamond Compound. 3 Micron and finer. Colour: Black.



NLH: A longer, stiffer nap cloth. Commonly used with 6 micron Kemet Diamond compound or finer. Colour: Cream.



NMH: A napped cloth with uni-directional fibres bonded to a cotton twill backing. A durable, wear resistant cloth. Commonly used with 6 micron Kemet Diamond compound or finer. Colour: Light Brown.



Selvyt SR: A cotton cloth of medium nap with a single pile. Available only as non-adhesive. Colour: Cream.



Chem H: For use with a chemical mechanical polishing process with colloidal silica suspension.

